

Updated Sensor Response Studies for SVT

Previous report on 2026.06.09 <https://indico.bnl.gov/event/33191/>

Introduction

2026.06.09:

- 10um epitaxial+40um substrate planar sensor in TCAD+GEANT4+Allpix² simulation
 - Sensor doping profiles tuned to have similar charge collection efficiency as a function of depth to a TZ65 nm CMOS sensor (H2M).
 - Sensor response to high energy charged particles:
 - Hit probability and cluster size from Allpix² compatible with pure GEANT4 simulation
 - Incident angle dependence of cluster size distribution from Allpix² compatible with ITS3 ER1 sensor measured with 120 GeV protons
 - Sensor response to low energy photons:
 - Hit probability and cluster size distribution from Allpix² largely different from GEANT4

Today:

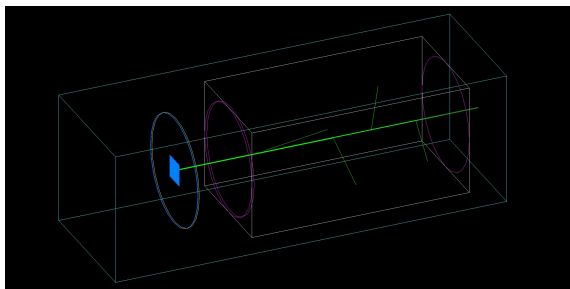
- Updates on low energy photon studies:
 - Allpix² bug fix and comparison of cluster size distribution to ER1 source measurements
 - Impact of Cu layers in the sensor on hit probability and cluster size
 - Eqv. active Si thickness in pure GEANT4 to have compatible hit probability as Allpix²

Tools Used In This Study - Reminder

Particles interaction with silicon



40 μm inactive + 10 μm active Si with
20x20 μm^2 pixels

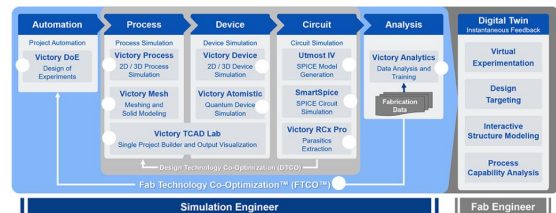


10 E_γ @ 80 keV

Sensor Doping profile and E-field

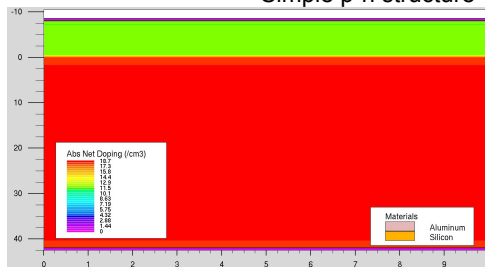
Semiconductor Process and Device Simulation

TCAD software solutions are key to developing new semiconductor processes and devices, dramatically reducing costs and time to market.



comprehensive suite of **Technology Computer-Aided Design (TCAD)** software tools to model semiconductor fabrication processes and device behaviors

Simple p-n structure



Transport model + Detector Response



Geometry Definition

Layout, materials

GEANT4 Wrapper

position + E_{dep}

Signal Formation

Charge $\rightarrow$ electrical signal

Charge Transport

Drift, diffuse...

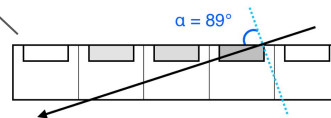
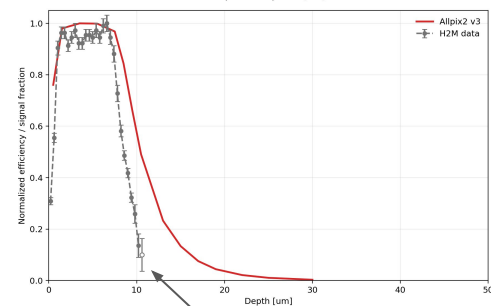
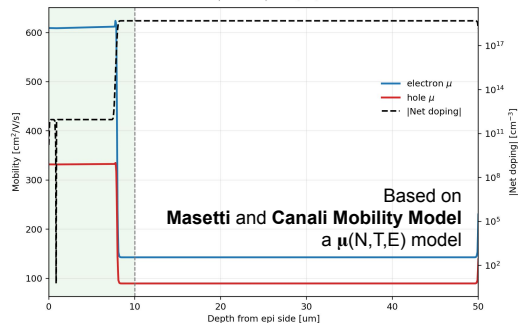
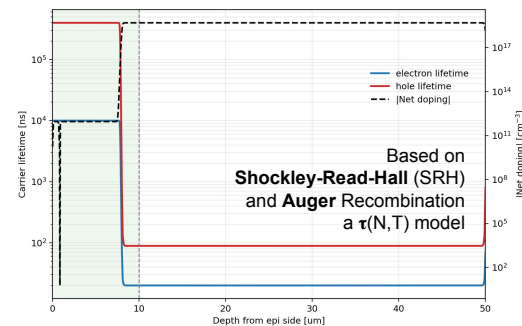
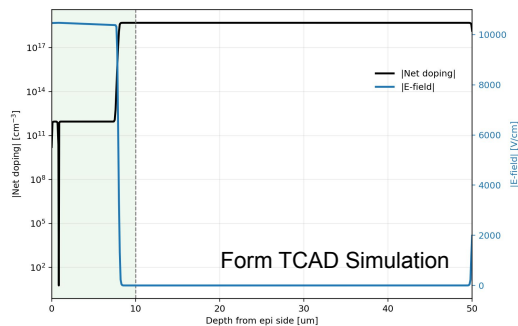
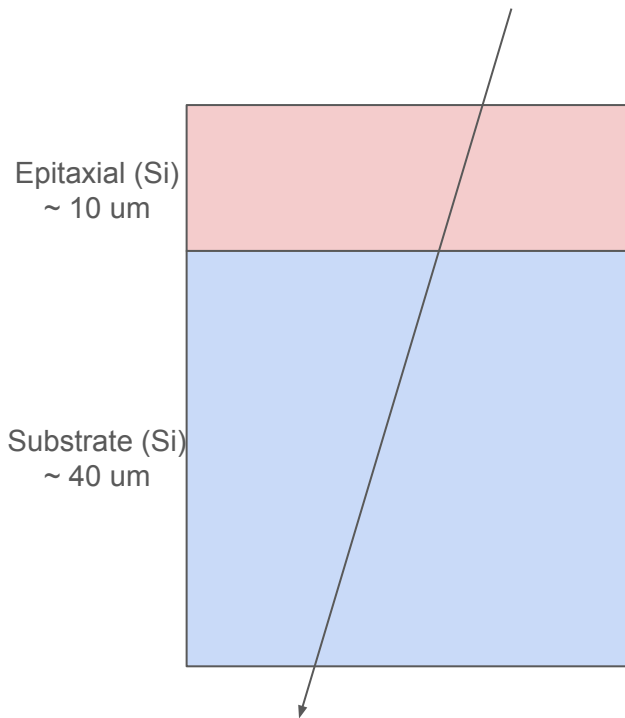
Digitization

Thr. Noise, Elec response

Output

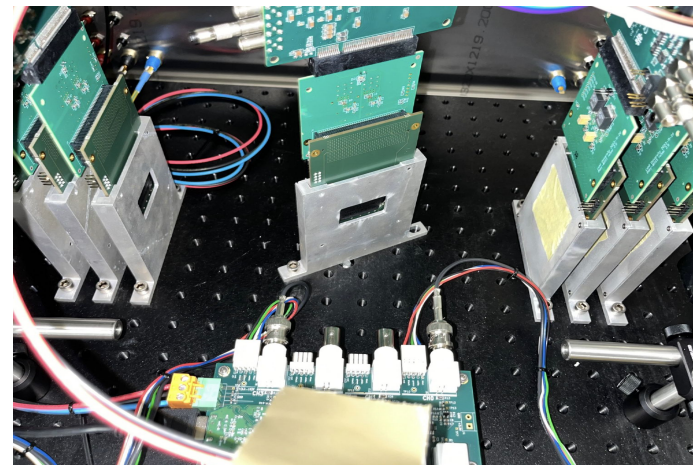
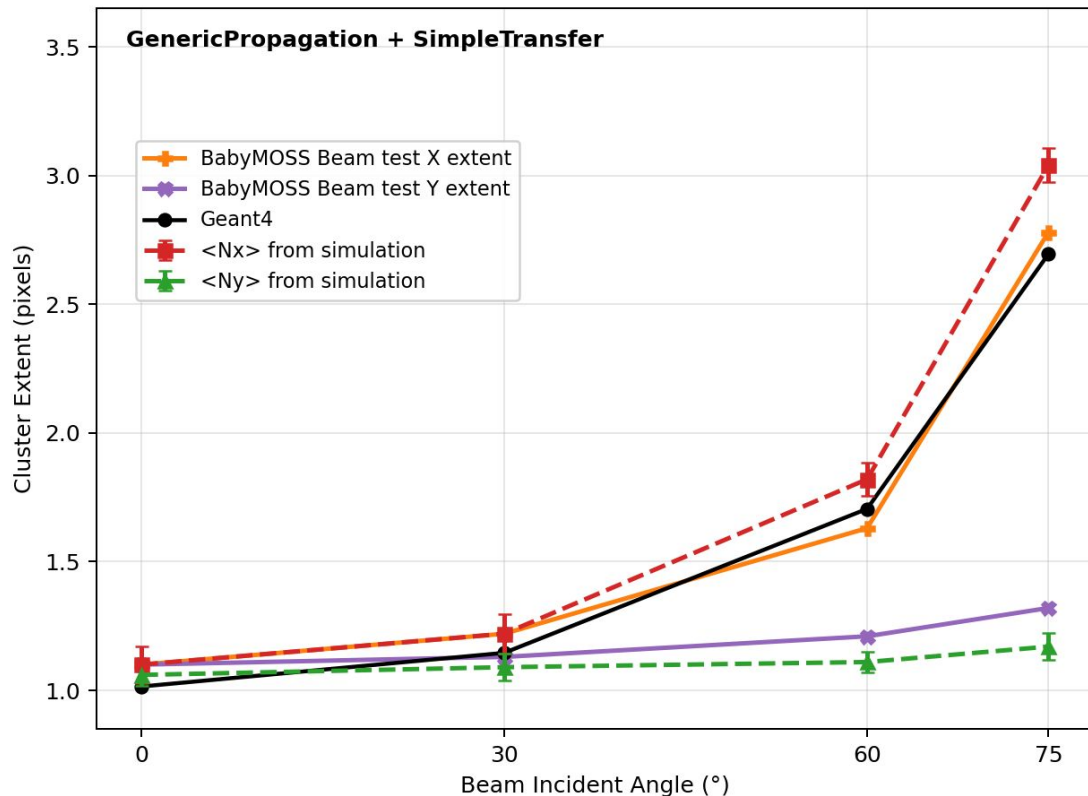
w. ROOT

TCAD+Allpix²+GEANT4 for Epitaxial and Substrate Silicon



The doping densities are based on ITS2 sensors (TZ180nm): NIMA 950 (2020) 162882, NIMA 988 (2021) 164859
The epitaxial layer thickness is tuned to H2M (TZ65nm) beam test data: doi:10.3204/PUBDB-2025-03980

High Energy Charged Particles (120 GeV protons)

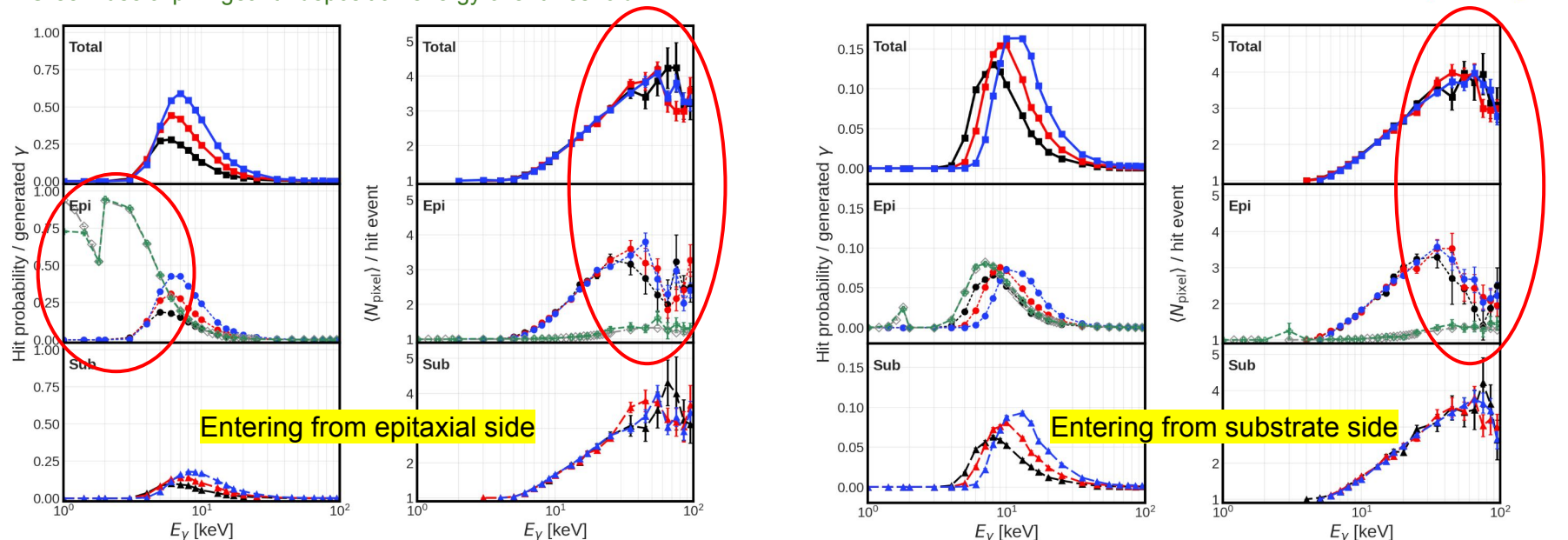


- Allpix² compatible with ER1 beam test data with 120 GeV protons, and with pure GEANT4 simulation
- Slightly higher <Nx> and lower <Ny> in simulation than data could partially be due to misalignment of the sensor w.r.t. beam

Low Energy Photons - Buggy Results

Grey: pure GEANT4 simulation

Green: use allpix2 geant4 deposition energy over threshold

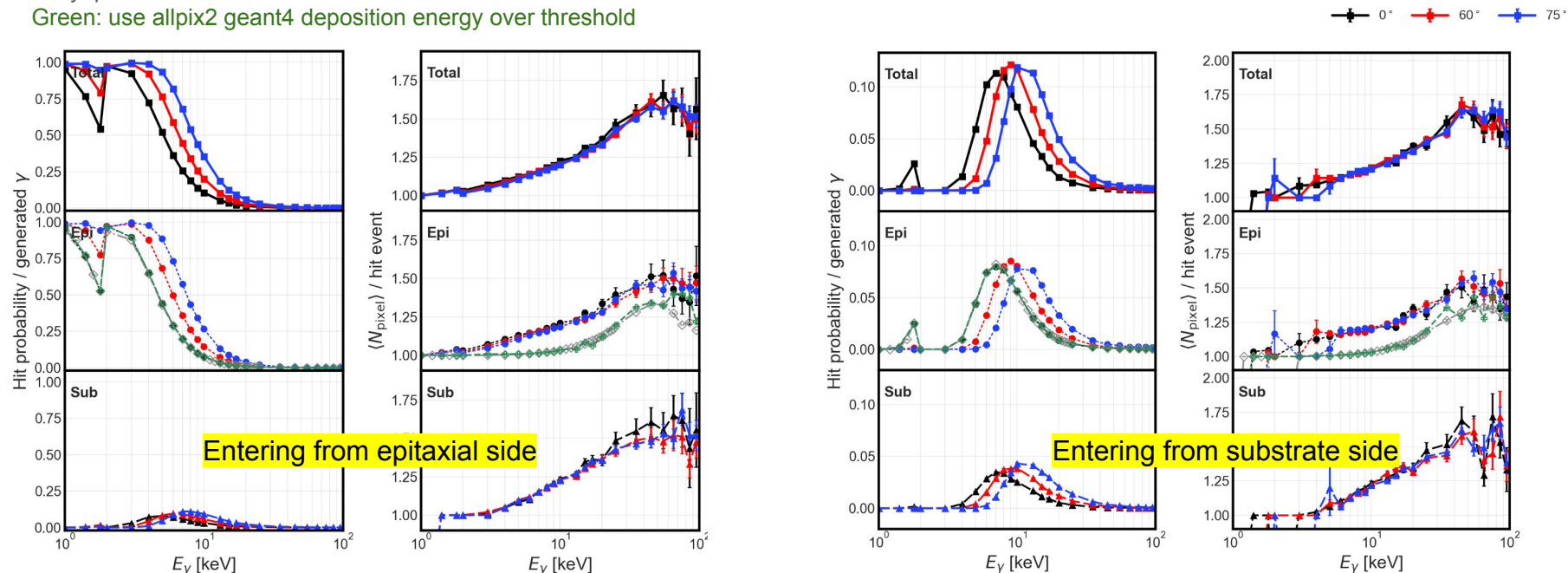


A bug found in the previous Allpix² simulation for low energy photons (charged particle simulation is not affected) where the E-field configuration was incorrect

Low Energy Photons - Corrected Results

Grey: pure GEANT4 simulation

Green: use allpix2 geant4 deposition energy over threshold

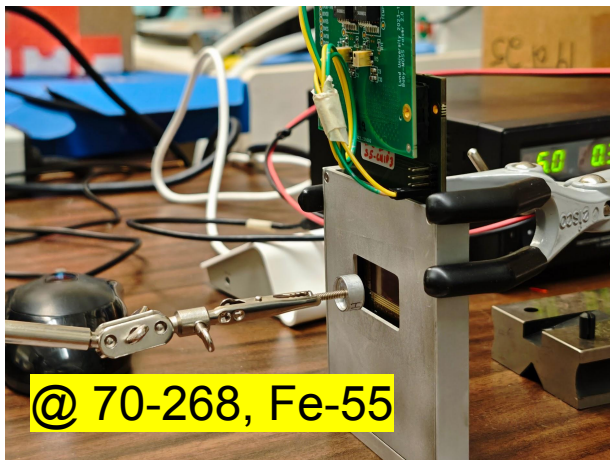


Significant dependence of cluster size on photon energy

Negligible dependence of cluster size on incident angle

Fe-55 & Am-241 Source Measurements with ER1 Sensor

- Chip & Boards: W21D4 S5-CHIP3 + 22 + RNC22
- **Bias: 0V** at room temperature
- DACS: IBIAS 62; IBIASN 100, IBD 50, IRESET 10; **VCASB 15**, VCASN 104; VS 145 - same as cern configuration
- Fe-55: $\gamma \sim 5.9$ keV;
- Am-241: $\gamma \sim 59.54$ keV, 17.75keV, etc

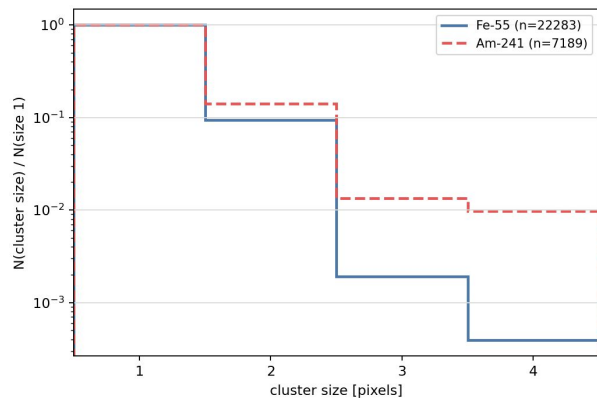


*The THR scan is not done for this sensor, so threshold might be different from 0.54 keV as in simulation

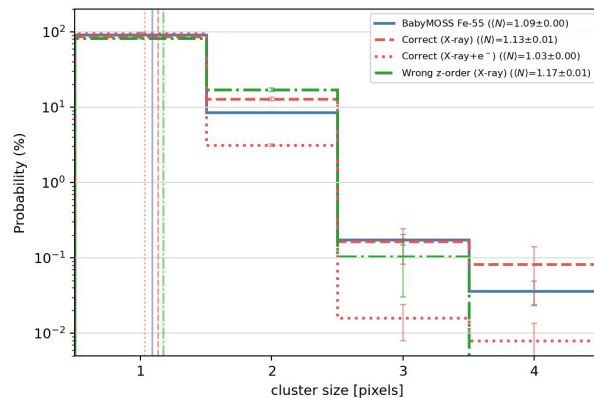
Fe-55 & Am-241 Source Measurements with ER1 Sensor

bias=0 V, Vcasb=15, background-subtracted

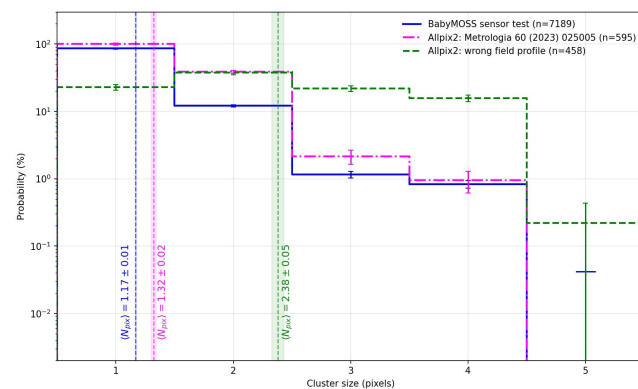
Source measurements



Fe-55 source



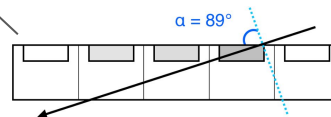
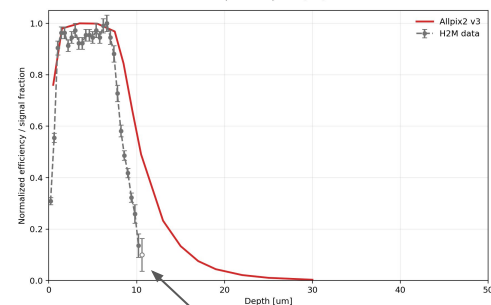
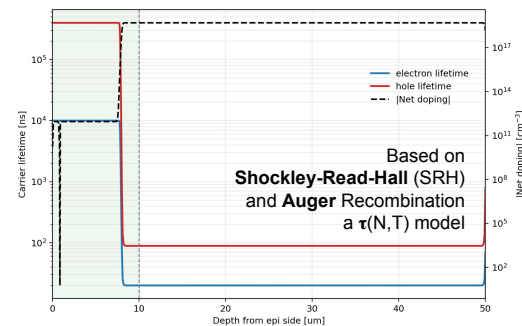
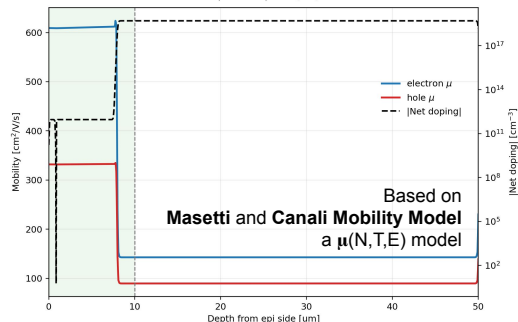
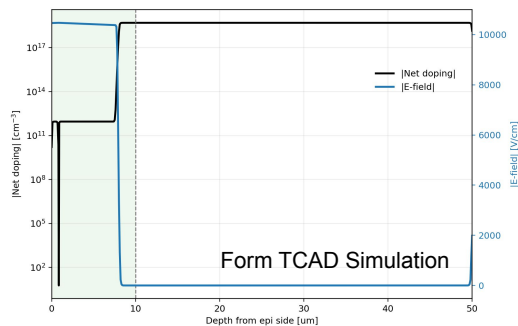
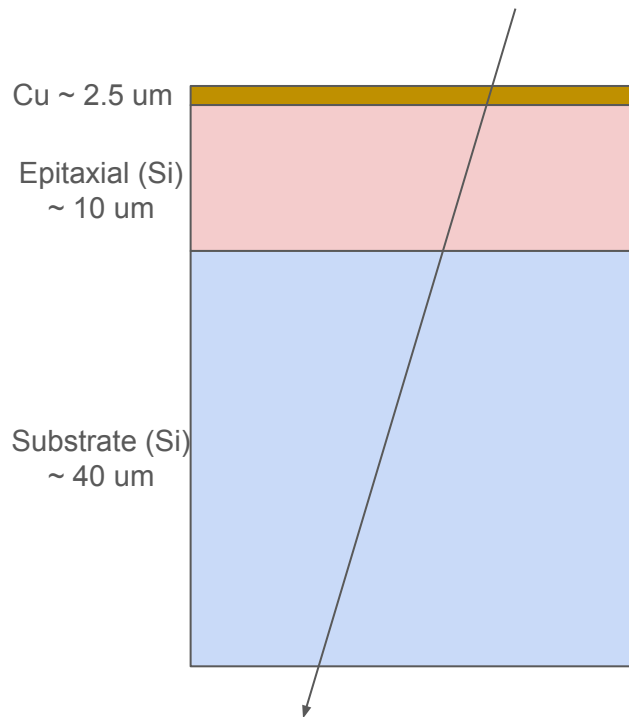
Am-241 source



- Cluster size distributions measured with Fe-55 and Am-241 are compatible with those from the corrected Allpix² simulation

*The THR scan is not done for this sensor, so threshold might be different from 0.54 keV as in simulation

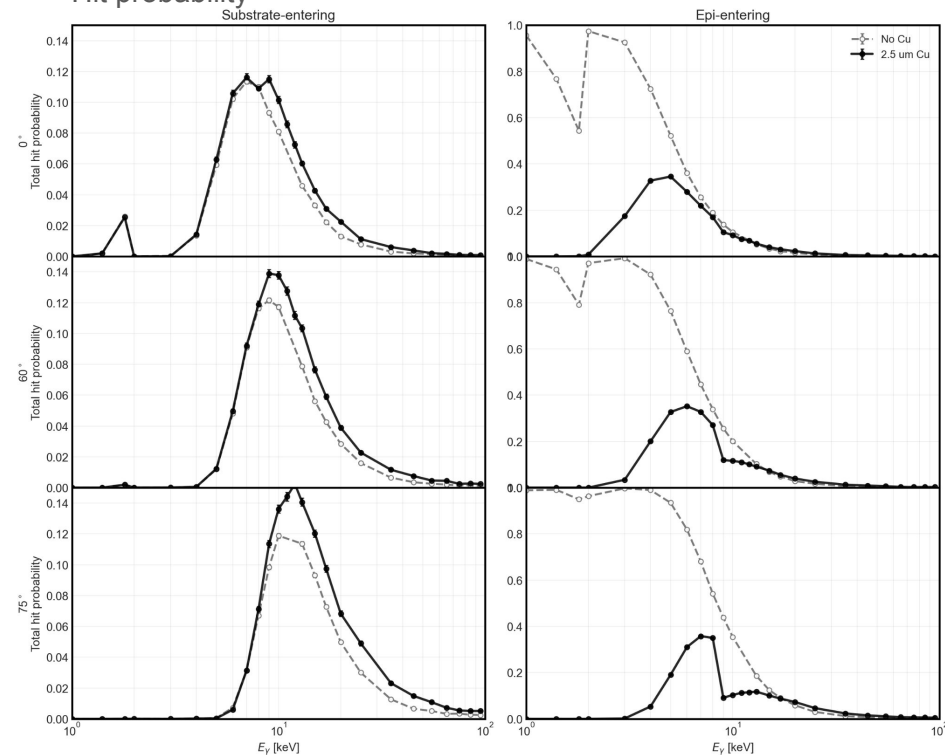
TCAD+Allpix²+GEANT4 Simulation w. 2.5 μm Cu



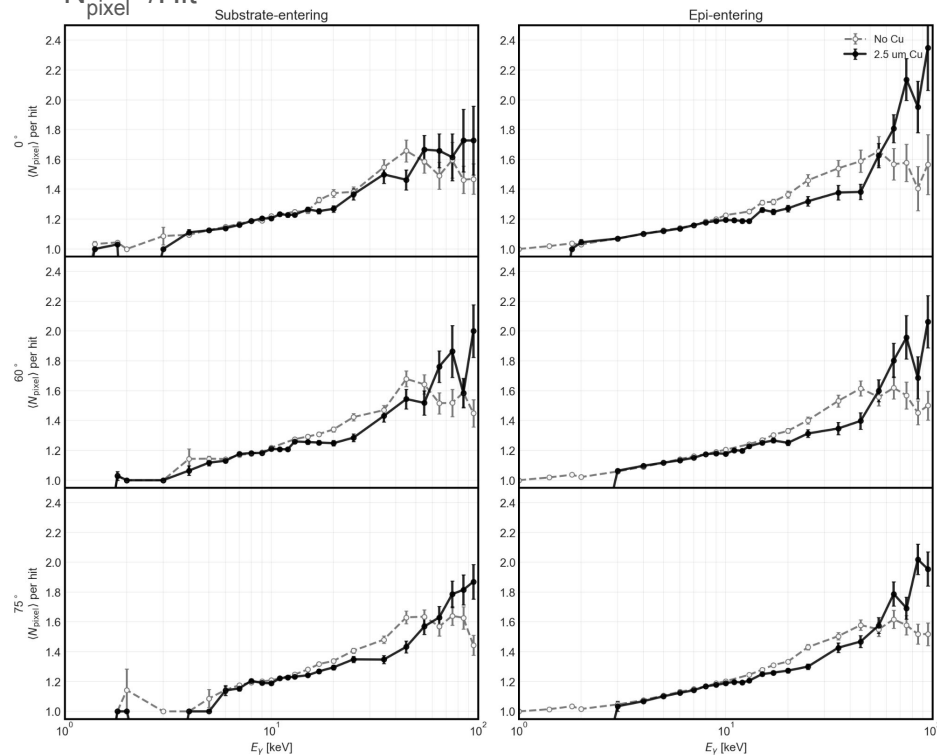
The doping densities are based on ITS2 sensors (TZ180nm): NIMA 950 (2020) 162882, NIMA 988 (2021) 164859
The epitaxial layer thickness is tuned to H2M (TZ65nm) beam test data: doi:10.3204/PUBDB-2025-03980

Low Energy Photons in Allpix² - w./w.o. 2.5um Cu layer

Hit probability



$\langle N_{\text{pixel}} \rangle / \text{Hit}$



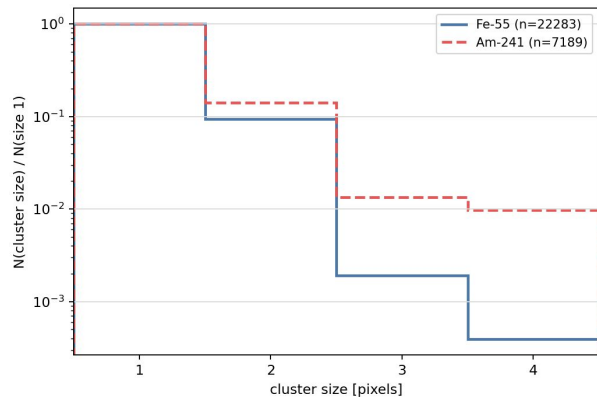
Element 29: Cu Atomic mass: 63.5460

Edge	keV	A
K	8.9789	1.3808
L-I	1.0961	11.3114

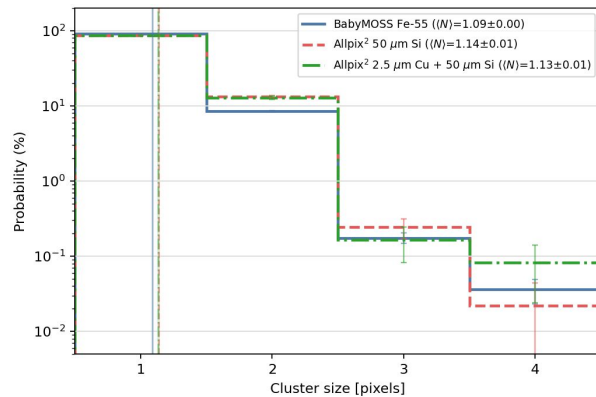
<http://skuld.bmsc.washington.edu/scatter/data/Cu.html>

Low Energy Photons in Allpix² - w. 2.5μm Cu

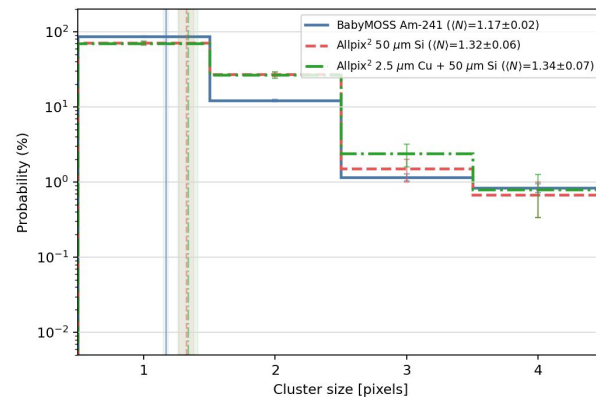
Source measurements



Fe-55 source



Am-241 source



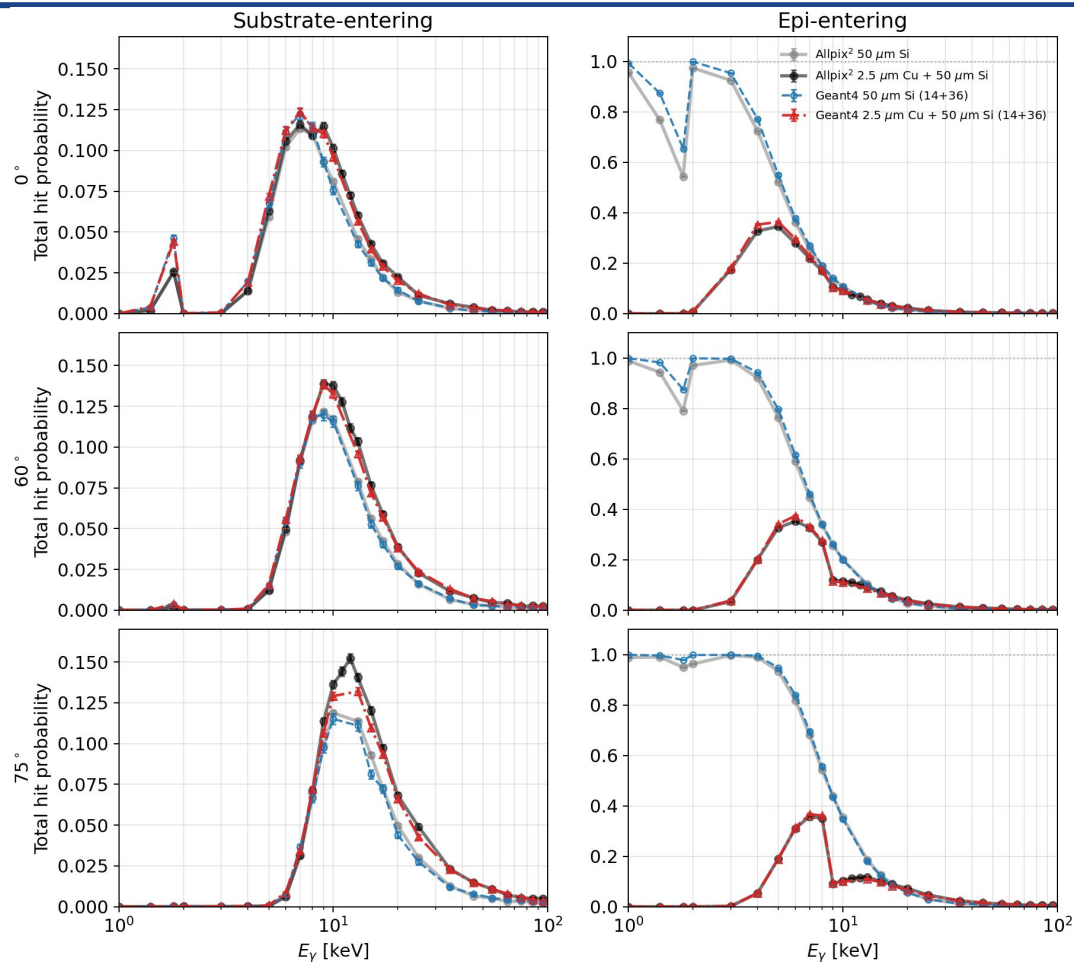
- Little change in cluster size distribution after adding the Cu layer in Allpix². Results from Allpix² are still compatible with ER1 source measurements

*The THR scan is not done for this sensor, so threshold might be different from 0.54 keV as in simulation

Summary and Outlook

- It is important to get SVT sensor response correct in simulation for SVT data rate estimation, as the latter strongly depend on hit probability and cluster size
- We have attempted to use TCAD+GEANT4+Allpix2 to understand sensor responses to high energy charged particles and low energy photons
 - Initial results on cluster size compatible with high energy charged particles (120 GeV protons) and low energy X-ray source (Fe-55, Am-241) measurements. We have not checked hit probability for low energy photons - difficult to do with radiative sources
 - To have an accurate accounting of hit probability and cluster sizes and thus data rates, we should measure them on ER2/Final sensors in SVT running conditions with charged particle beam and synchrotron light source, and improve the simulation with realistic sensor structure when we have access to foundry doping profiles
- Impractical to adopt TCAD+GEANT4+Allpix2 for ePIC simulation - rely on DD4Hep GEANT4
 - A sensor structure with 2.5um Cu + 14um active Si + 36um inactive Si in pure GEANT4 simulation gives compatible hit probabilities as full Allpix2 simulation (see next page)
 - More involved to describe cluster size - 3D sensor charge collection efficiency map, or particle specie+energy+incident angle dependent parameterization?

Match Hit Probability in GEANT4 with the Alpex2 Simulation

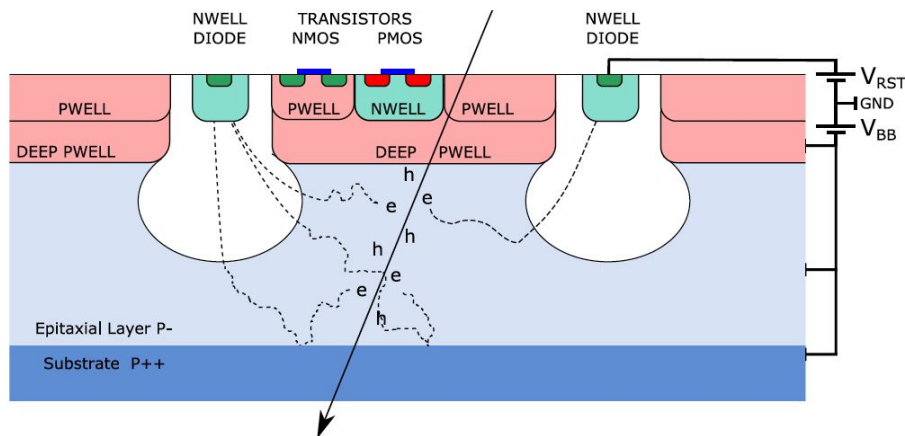


Compare **black** with **red**

Pure GEANT4 simulation with 2.5 μ m Cu
+ 14 μ m active Si + 36 μ m inactive Si

matches with Alpex2 hit probability (w.
Simple p-n structure) relatively well

Introduction



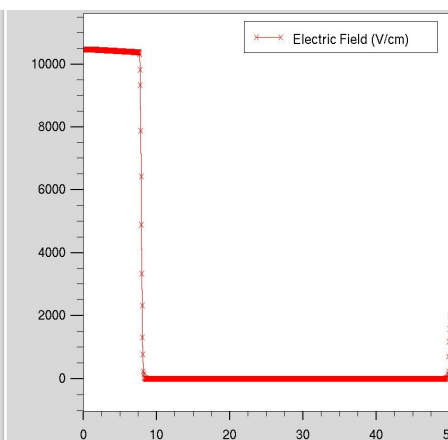
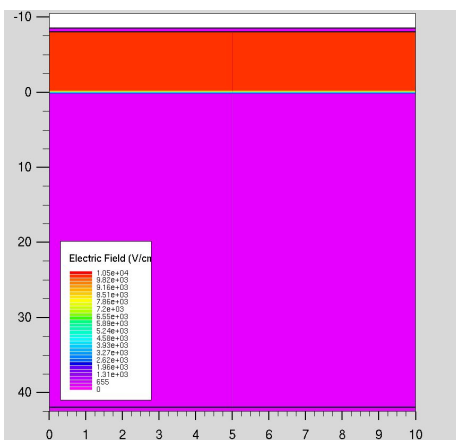
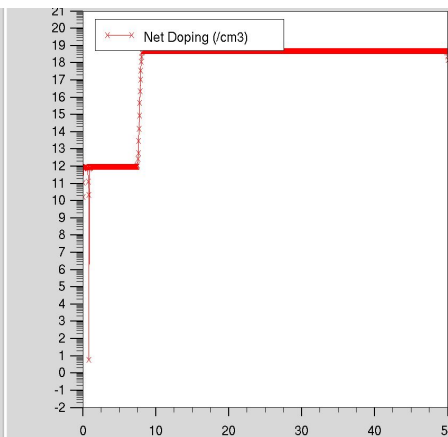
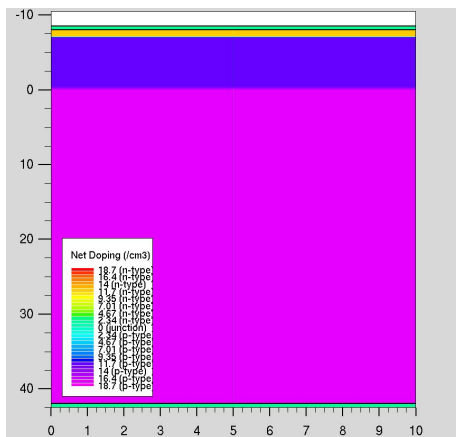
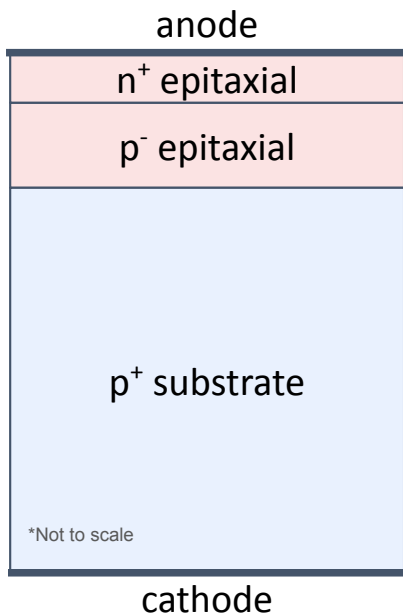
- P/N-well: high doping, electrical circuit
- Epitaxial: low doping, sensor active volume
- Substrate: high doping, mechanical handling

1. Particles interact with sensor and generate signal charges [1]
2. Signal charges collected through drifting and diffusion [2-7]
3. Collected charges are processed by integrated readout electronics

References

- [1] *Passage of Particles Through Matter*, S. Navas et al. (Particle Data Group), *Phys. Rev. D* 110, 030001 (2024)
- [2] *Simulation and measurements of charge collection in monolithic active pixel sensors*, Grzegorz Deptuch et al., *NIMA* 465 (2001) 92–100
- [3] *New Generation of Monolithic Active Pixel Sensors for Charged Particle Detection*, Grzegorz Deptuch (2002).
- [4] *Study of Monolithic Active Pixel Sensors for the Upgrade of the ALICE Inner Tracking System*, Miljenko Šuljić, CERN-THESIS-2017-304
- [5] *MC simulation of charge collection processes in Monolithic Active Pixel Sensors for the ALICE ITS upgrade*, Miljenko Šuljić, *NIMA* 950 (2020) 162882
- [6] *Development and performance study for the ALICE ITS3: the first truly cylindrical inner tracker*, Isabella Sanna, CERN-THESIS-2024-359
- [7] *TCAD and charge transport simulations of MAPS in 65nm for the ALICE ITS3*, Isabella Sanna et al., *JINST* 20 (2025) C06032

Doping and E-field from Silvaco TCAD Simulation



We don't know the manufacture process and doping profiles for ITS3 sensors made from TowerJazz 65 nm process

The following study uses a simple p-n structure to get carrier drifting, diffusion, and recombination parameters.

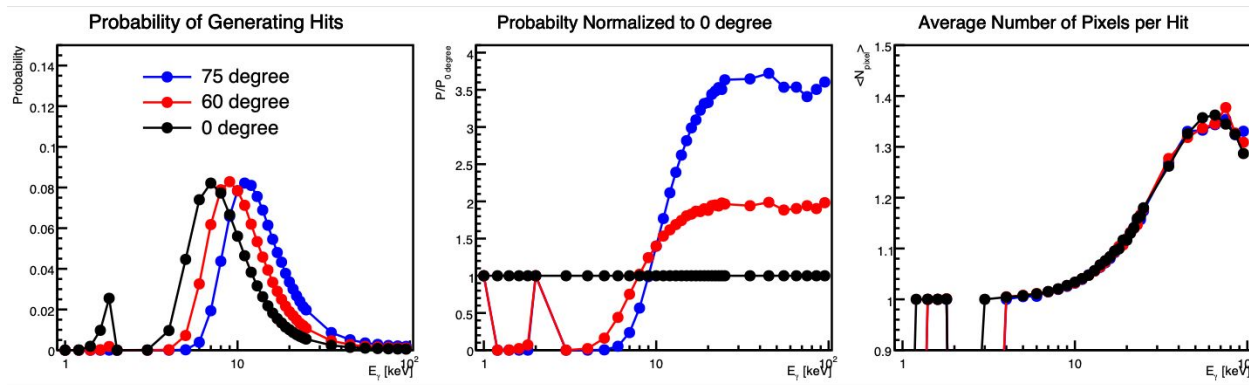
The doping densities are based on MAPS sensors made from TZ180nm process:

NIMA 950 (2020) 162882

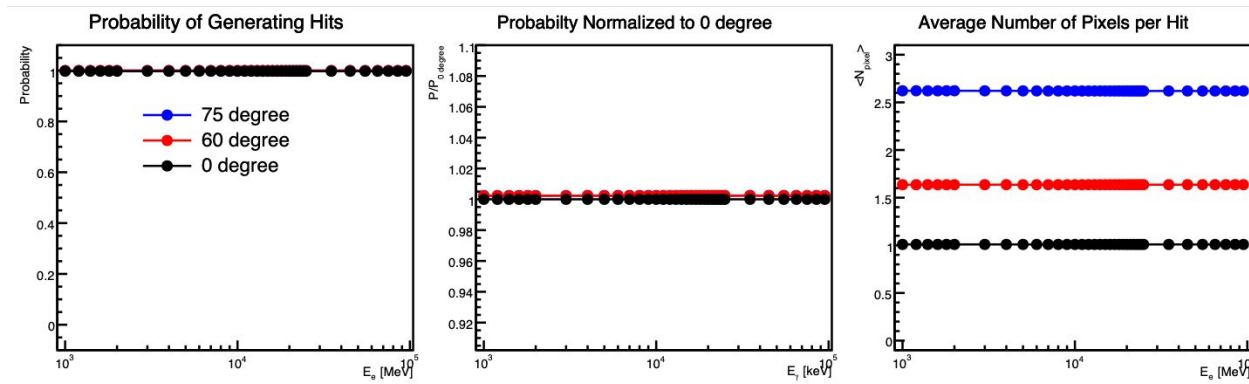
NIMA 988 (2021) 164859

Particle Interaction with Silicon (GEANT4)

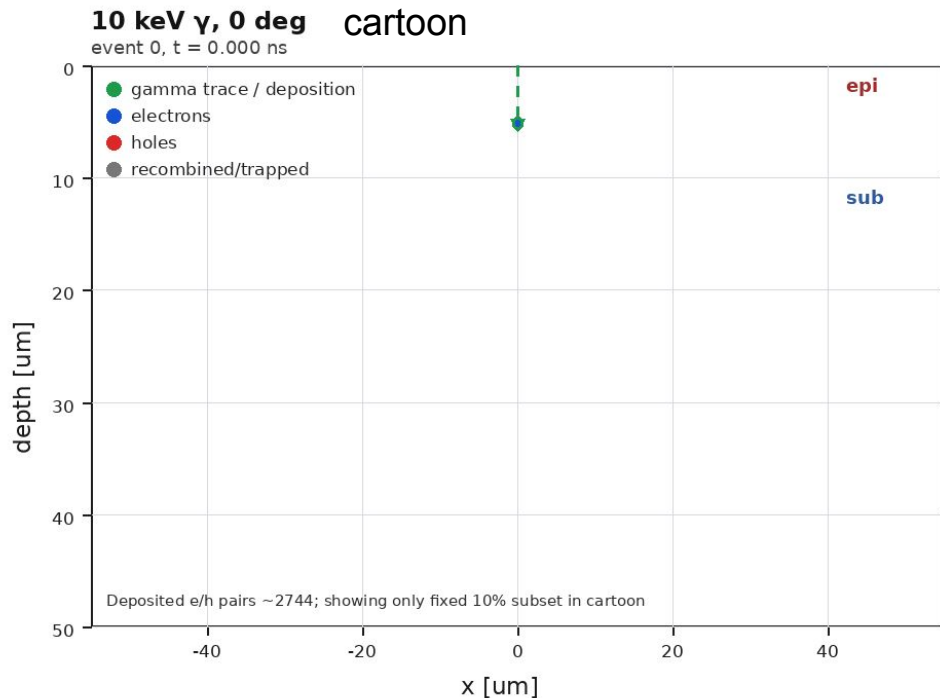
Low-Energy Photon



High-Energy Electron



Interaction with Particle and Charge Transport via AllPix2

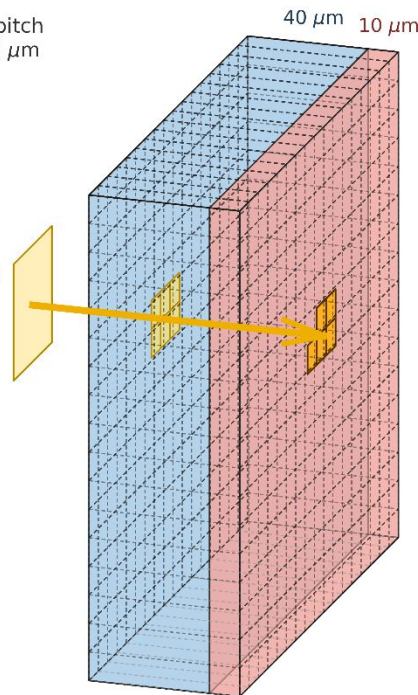


Substrate-side entry

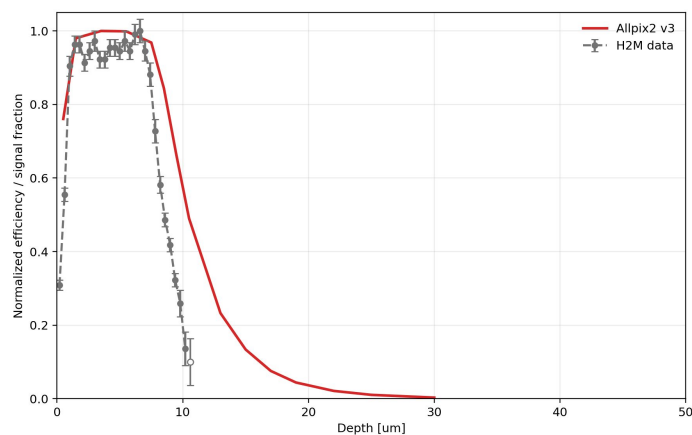
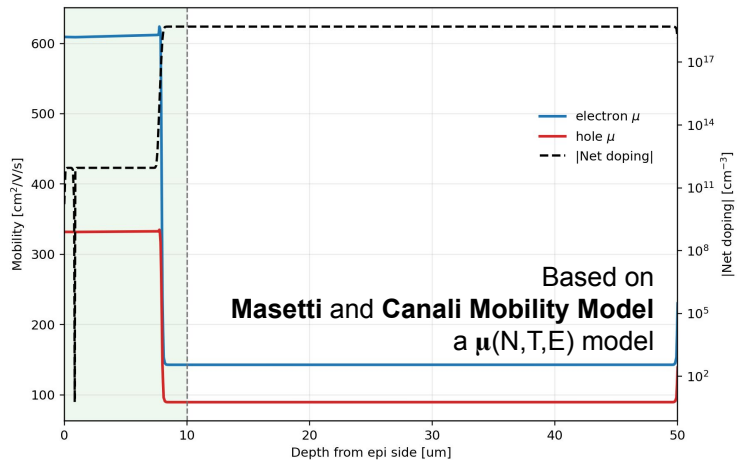
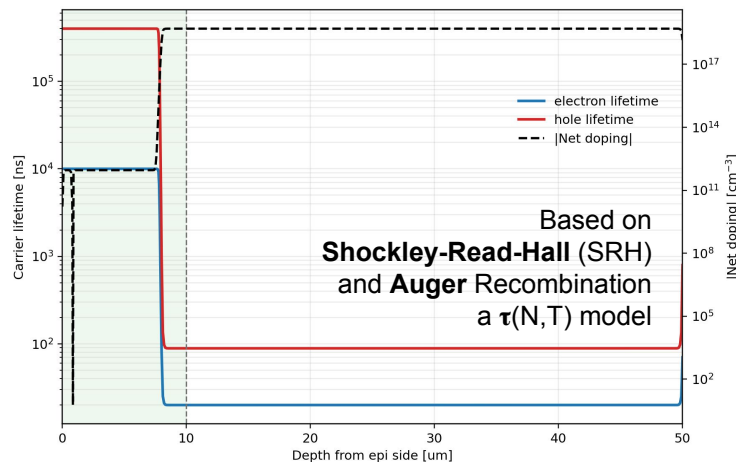
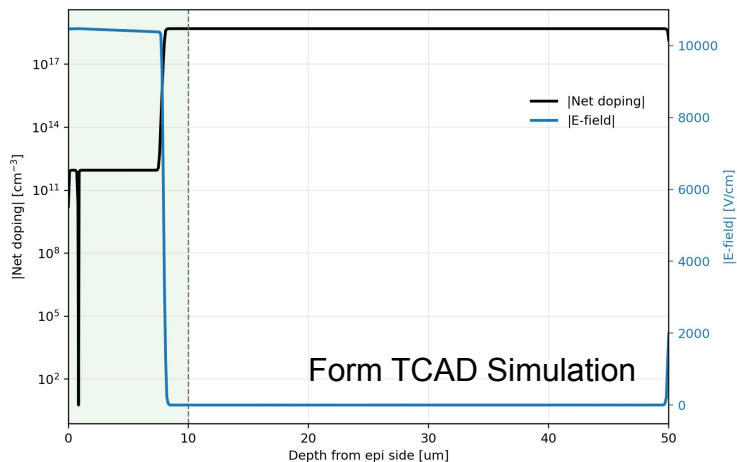
101 x 101 pixels, 20 μm pitch
source plane: 60 μm x 60 μm

- Substrate
- Epitaxial layer
- γ source / entry light
- Hit/readout pixels

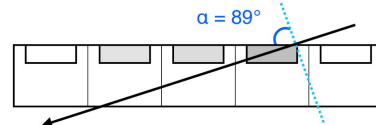
Not to scale



Doping profile, E-fields, and Carrier Mobility in AllPix2



H2M (TZ65nm) beam test data:
doi:10.3204/PUBDB-2025-03980



Fe-55 & Am-241 Sources

Fe-55

Dataset #1:

Author: Huo Junde Citation: Nuclear Data Sheets 109, 787 (2008)

Parent Nucleus	Parent E(level)	Parent J^π	Parent $T_{1/2}$	Decay Mode	GS-GS Q-value (keV)	Daughter Nucleus	Decay Scheme	ENSDF file
$^{55}_{26}\text{Fe}$	0.0	3/2-	2.744 y 9	ϵ : 100 %	231.21 18	$^{55}_{25}\text{Mn}$		

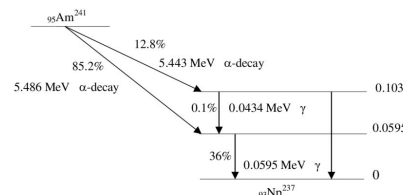
Electrons:

	Energy (keV)		Intensity (%)		Dose (MeV/Bq-s)
Auger L	0.61		139.9 % 14		8.53E-4 8
Auger K	5.19		60.1 % 8		0.00312 4

Gamma and X-ray radiation:

	Energy (keV)		Intensity (%)		Dose (MeV/Bq-s)
XR L	0.64		0.66 % 10		4.2E-6 6
XR $\text{K}\alpha_2$	5.888		8.2 % 4		4.85E-4 21
XR $\text{K}\alpha_1$	5.899		16.2 % 7		9.6E-4 4
XR $\text{K}\beta_1$	6.49		1.89 % 9		1.23E-4 6
XR $\text{K}\beta_3$	6.49		0.96 % 5		6.3E-5 3
	126.0 1		1.280E-7 % 20		1.61E-10 3

Am-241



IOP Publishing | Bureau International des Poids et Mesures
Metrologia 60 (2023) 025005 (18pp)

Metrologia
<https://doi.org/10.1088/1681-7575/acb99>

Determination of absolute Np L x-ray emission intensities from ^{241}Am decay using a metallic magnetic calorimeter

Matias Rodrigues*, Martin Loidl and Sylvie Pierre

Université Paris-Saclay, CEA, List, Laboratoire National Henri Becquerel (LNE-LNHB), F-91120 Palaiseau, France

